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SEMICONDUCTOR WAFER WASHING EQUIPMENT

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ABSTRACT

PURPOSE: To enable removing minute particles in a liquid and perfectly replacing a washing liquid between treatment processes by synthesizing the washing liquid using a gas and very pure water in a treatment tank.

CONSTITUTION: A retainer 3 which holds and rotates a semiconductor wafer 2, a water supply nozzle 9 which spouts very pure water in a foggy state, gas cylinders 6, 10, 11 which contain various reactive gases for the raw materials of a washing liquid, a vaporizer 12 which evaporates anhydrous hydrofluoric acid and a gas filter 5 which removes minute particles during evaporation are provided. The washing liquid is synthesized by mixing the reactive gases and the evaporated anhydrous hydrofluoric acid spouted in a treatment tank 1 and the very pure water spouted from the water supply nozzle 9. This can reduce the number of the minute particles and can more perfectly replace a washing agent between treatment processes since evaporation is used.

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